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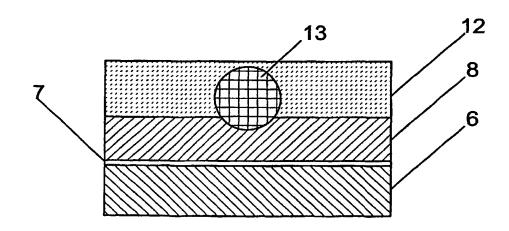
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With international search report.

(54) Title: WAVEGUIDE FOR AN OPTICAL CIRCUIT AND METHOD OF FABRICATION THEREOF

(57) Abstract

A waveguide for an optical circuit comprises a substrate; a buffer layer formed on the substrate; a doped lower cladding layer formed on the buffer layer; a doped waveguide core formed on the lower cladding layer; and a doped upper cladding layer embedding the waveguide core. The waveguide core includes mobile dopant ions which have diffused into the upper cladding layer and the lower cladding layer to form an ion diffusion region around said waveguide core such that the waveguide core boundary walls are substantially smooth. A waveguide core may be formed



which is substantially symmetric about its core axis. Methods of fabricating the waveguide are also described.

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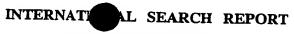
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C. DOCUM	ENTS CONSIDERED TO BE RELEVANT				
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اتا	her documents are listed in the continuation of box C.	Patent family m	nembers are listed i	in annex.	
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Name and m	nailing address of the ISA European Patent Office, P.B. 5818 Patentlaan 2 NL – 2280 HV Rijswijk Tel. (+31-70) 340–2040, Tx. 31 651 epo nl, Fax: (+31-70) 340–3016	Authorized officer Jakober,	, F		



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information on patent family members

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JP 62124511	A	05-06-1987	JP	2622108 B	18-06-1997

P. INT COOPERATION TREAT

	From the INTERNATIONAL BUREAU				
PCT	То:				
NOTIFICATION OF ELECTION (PCT Rule 61.2)	Assistant Commissioner for Patents United States Patent and Trademark Office Box PCT Washington, D.C.20231 ETATS-UNIS D'AMERIQUE				
Date of mailing (day/month/year) 03 October 2000 (03.10.00)	in its capacity as elected Office				
International application No. PCT/GB00/00322	Applicant's or agent's file reference P23051A/VSL/CLF/PPP				
International filing date (day/month/year) 07 February 2000 (07.02.00)	Priority date (day/month/year) 05 February 1999 (05.02.99)				
Applicant					
DA SILVA MARQUES, Paulo, Vicente et al					
1. The designated Office is hereby notified of its election made: X in the demand filed with the International Preliminary Examining Authority on: 04 September 2000 (04.09.00) in a notice effecting later election filed with the International Bureau on:					
2. The election X was was not was not made before the expiration of 19 months from the priority Rule 32.2(b).	date or, where Rule 32 applies, within the time limit under				
The International Bureau of WIPO 34, chemin des Colombettes 1211 Geneva 20, Switzerland	Authorized officer S. Mafla				

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INTERNATIONAL PRELIMINARY EXAMINATION REPORT

(PCT Article 36 and Rule 70)

Applicant's or agent's file reference P23051A/VSL/CLF/PPP	FOR FURTHER ACTION	See Notification of Transmittal of International Preliminary Examination Report (Form PCT/IPEA/416)
	International filing date (day/mon	th/year) Priority date (day/month/year)
International application No. PCT/GB00/00322	07/02/2000	05/02/1999
International Patent Classification (IPC) or G02B6/13	national classification and IPC	
Applicant		
THE UNIVERSITY COURT OF THE	HE UNIVERSITY OF et al.	
This international preliminary exa and is transmitted to the applican	mination report has been prepare t according to Article 36.	ed by this International Preliminary Examining Authority
2. This REPORT consists of a total	of 6 sheets, including this cover	sheet.
been amended and are the b	pasis for this report and/or sheets 607 of the Administrative Instruc	the description, claims and/or drawings which have containing rectifications made before this Authority tions under the PCT).
This report contains indications report contains indications.	elating to the following items:	
। ⊠ Basis of the report		
Ⅱ □ Priority		
III Non-establishment o	of opinion with regard to novelty, i	nventive step and industrial applicability
IV 🗆 Lack of unity of inver		
V ⊠ Reasoned statement citations and explana	t under Article 35(2) with regard t ations suporting such statement	o novelty, inventive step or industrial applicability;
VI Certain documents	cited	
VII Certain defects in the	e international application	
VIII ⊠ Certain observations	on the international application	
	Data	of completion of this report
Date of submission of the demand	Date	or completion or this report
04/09/2000	25.05	.2001
Name and mailing address of the internation	onal Autho	rized officer
preliminary examining authority: European Patent Office - P.E NL-2280 HV Rijswijk - Pays Tel. +31 70 340 - 2040 Tx: 3	3. 5818 Patentlaan 2 Bas Jako	ober, F
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International application No. PCT/GB00/00322

I. Basis of the report

1.	With regard to the elements of the international application (Replacement sheets which have been furnished to the receiving Office in response to an invitation under Article 14 are referred to in this report as "originally filed" and are not annexed to this report since they do not contain amendments (Rules 70.16 and 70.17)): Description , pages:							
	1-21		as originally filed					
	Clai	ms, No.:						
	1-80)	with telefax of	06/02/2001				
	Dra	wings, sheets:						
	1/3-	3/3	as originally filed					
2.	With lang	n regard to the lang Juage in which the	guage, all the elemen international applicati	ts marked above were available or furnished to this Authority in the on was filed, unless otherwise indicated under this item.				
	The	se elements were a	available or furnished	to this Authority in the following language: , which is:				
		the language of a	translation furnished	for the purposes of the international search (under Rule 23.1(b)).				
		the language of pu	ublication of the interr	ational application (under Rule 48.3(b)).				
		the language of a 55.2 and/or 55.3).		for the purposes of international preliminary examination (under Rule				
3.	With	n regard to any nuc rnational prelimina	cleotide and/or amin ry examination was c	o acid sequence disclosed in the international application, the arried out on the basis of the sequence listing:				
		contained in the ir	nternational applicatio	n in written form.				
		filed together with	the international app	ication in computer readable form.				
		furnished subsequ	uently to this Authority	in written form.				
		furnished subsequ	uently to this Authority	in computer readable form.				
			at the subsequently fu application as filed has	rnished written sequence listing does not go beyond the disclosure in s been furnished.				
		The statement that listing has been fu		orded in computer readable form is identical to the written sequence				
4.	The	amendments have	e resulted in the canc	ellation of:				
		the description,	pages:					
		the claims,	Nos.:					



International application No. PCT/GB00/00322

		the drawings,	sheets:		
5.		considered to go bey	ond the dis	sclosure a	ome of) the amendments had not been made, since they have been as filed (Rule 70.2(c)):
		(Any replacement sh report.)	eet contain	ing such	amendments must be referred to under item 1 and annexed to this •
6.	Add	ditional observations, i	f necessary	y:	
٧.	Rea cita	asoned statement un ations and explanatio	der Article	e 35(2) wi	ith regard to novelty, inventive step or industrial applicability; h statement
1.	Sta	tement			
	No	velty (N)	Yes: No:	Claims Claims	1-80
	Inv	entive step (IS)	Yes: No:	Claims Claims	1-80
	Ind	lustrial applicability (IA) Yes: No:	Claims Claims	1-80
2.	Cit	ations and explanation	าร		

VII. Certain defects in the international application

see separate sheet

The following defects in the form or contents of the international application have been noted: see separate sheet

VIII. Certain observations on the international application

The following observations on the clarity of the claims, description, and drawings or on the question whether the claims are fully supported by the description, are made: see separate sheet

INTERNATIONAL PRELIMINARY **EXAMINATION REPORT - SEPARATE SHEET**

Re Item V

Reasoned statement under Rule 66.2(a)(ii) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

Reference is made to the following documents:

D1: JP(A) 59137346

D2: Ieee Photonics Technology Letters, us, ieee Inc. New York (01-08-1992),

4(8), 875-877

D3: IBM Technical Disclosure Bulletin, us, ibm Corp. New York (01-08-1990),

33(3A), 199-

D4: JP(A) 60191208 D5: JP(A) 62124511

- Document D1, which is considered to represent the most relevant state of the art, 1. discloses a waveguide comprising:
 - a substrate.
 - a lower cladding layer
 - a doped waveguide core formed on the lower cladding
 - an upper cladding layer embedding the waveguide core
 - wherein the waveguide core includes mobile dopant ions which have diffused into the upper and lower cladding layers forming a waveguide core having smooth boundary walls.

from which the subject-matter of claim 1 differs in that the lower and upper cladding layers are doped.

As explained in the description of the application, the doping of the cladding layers permits the control of the dopant diffusion (page 3, line 33 to page 4, line 2 of the description).

However, it is well known to a skilled person, that the diffusion of a dopant in a material depends on the concentration of dopant within this material (see in particular document D2). A skilled person would adjust the concentration depending of the parameters he wants to obtain.

Claim 1 further precises that the lower layer is a deposited layer. This feature is

EXAMINATION REPORT - SEPARATE SHEET

only an obvious possibility for the fabrication of the lower layer. A deposited layer and the adjustment of the dopant concentration are independent features and their combination does not lead to any particular surprising or unexpected effect. The subject-matter of claim 1 can not be considered as involving an inventive step (Art. 33.2 PCT).

- For the same reason, the subject-matter of claim 30 does not involve an inventive 2. step.
- It would appear that the dependent claims do not define subject-matter which is 3. inventive, since their structural features are either known from documents cited in the search report or obvious modifications (see passages cited in the international search report).

Re Item VII

Certain defects in the international application

- Contrary to the requirements of Rule 5.1(a)(ii) PCT, the relevant background art 1. disclosed in the documents D1, D2 is not mentioned in the description, nor are these documents identified therein.
- Independent claims 1 and 30 are not in the two-part form in accordance with Rule 2. 6.3(b) PCT, which in the present case would be appropriate, with those features known in combination from the prior art (document D1) being placed in the preamble (Rule 6.3(b)(i) PCT) and with the remaining features being included in the characterising part (Rule 6.3(b)(ii) PCT).
- The features of the claims are not provided with reference signs placed in 3. parentheses (Rule 6.2(b) PCT).

Re Item VIII

Certain observations on the international application

The "spirit clause" (page 20 and 21) should have been deleted as its presence in 1.

INTERNATIONAL PRELIMINARY

International application No. PCT/GB00/00322

EXAMINATION REPORT - SEPARATE SHEET

the description serves only to cast unnecessary doubt upon the intended scope of the claims (art. 6 PCT)

As they refer to a buffer layer, claims 7, 8, 9 should have been dependent on 2. claim 5 and claims 36, 42, 43, 44 on claim 35. Claim 62 should also have been dependent on claims referring to a buffer layer. This inconsistency in the claim dependency leads to unclarity (Art. 6 PCT).

- A waveguide for an optical circuit comprising:
 - a substrate;
 - a deposited doped lower cladding layer;
- a doped waveguide core formed from a layer of doped material deposited on the lower cladding layer; and
- a deposited doped upper cladding layer embedding the waveguide core;

wherein the waveguide core includes mobile dopant ions which have diffused from the deposited doped material of the waveguide core into the upper cladding layer and the lower cladding layer to form an ion diffusion region around said doped waveguide core such that the waveguide core boundary walls are substantially smooth.

- 2. A waveguide as claimed in Claim 1, wherein the ion diffusion region is isotropic with respect to the waveguide core, such that the waveguide core is substantially symmetric about the core axis.
- 3. A waveguide as claimed in either Claim 1 or Claim 2, wherein the ion diffusion region surrounding the waveguide core forms a substantially rounded waveguide core.
- 4. A waveguide as claimed in Claim 3, wherein the rounded waveguide core is elliptical or circular in cross-section.
- 5. A waveguide as claimed in any one preceding claim, further including a buffer layer formed on the substrate and wherein the lower cladding layer is formed on the buffer layer.

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- A waveguide as claimed in any one preceding claim, wherein the substrate comprises silicon and/or silica and/or sapphire.
- A waveguide as claimed in Claim 6, wherein said buffer 7. layer includes a thermally oxidised layer of the substrate.
- A waveguide as claimed in any preceding claim, wherein the buffer layer comprises doped silica.
- A waveguide as claimed in any preceding claim, wherein 9. the thickness of the buffer layer is in the range 0.2 $\mathfrak m$ to 20 m.
- 10. A waveguide as claimed in any preceding claim, wherein the lower cladding layer comprises doped silica.
- 11. A waveguide as claimed in any preceding claim, wherein the lower cladding layer includes at least one Phosphorus oxide and/or at least one Boron oxide.
- A waveguide as claimed in Claim 11, wherein the lower cladding layer includes at least one Phosphorus oxide and at least one Boron oxide and wherein the Phosphorus oxide to Boron oxide ratio is such that the lower cladding layer refractive index is substantially equal to the refractive index of the buffer layer.
- 13. A waveguide as claimed in any preceding claim, wherein the lower cladding layer includes doped silica, at least one Phosphorus oxide and at least one Boron oxide and wherein the silica: Phosphorus oxide: Boron oxide ratio is in

the range of 75 to 95 wt% silica:1 to 7 wt% Phosphorus oxide:4 to 18 wt% Boron oxide.

- 14. A waveguide as claimed in Claim 13, wherein the lower cladding layer has a silica: Phosphorus oxide: Boron oxide ratio in the range of 80 to 90 wt% silica: 2.5 to 6 wt% Phosphorus oxide: 7.5 to 14 wt% Boron oxide.
- 15. A waveguide as claimed in Claim 14, wherein the lower cladding layer has a silica; to Phosphorus oxide; to Boron oxide ratio of 82 wt% silica; to 5 wt% Phosphorus oxide; to 13 wt% Boron oxide.
- 16. A waveguide as claimed in any preceding claim, wherein the thickness of the lower cladding layer is 1 m to 20 m.
- 17. A waveguide as claimed in any preceding claim, wherein the waveguide core comprises doped silica.
- 18. A waveguide as claimed in any preceding claim, wherein said mobile dopant ions of the waveguide core include Phosphorus and/or Fluorine and/or compounds of these elements.
- 19. A waveguide as claimed in any preceding claim, wherein dopant ions of the waveguide core include Phosphorus and/or Fluorine and/or Aluminium and/or Boron and/or Germanium and/or Tin and/or Titanium and/or compounds of these elements.

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- A waveguide as claimed in any preceding claim, wherein the waveguide core includes Phosphorus oxide and/or Boron oxide.
- A waveguide as claimed in Claim 20, wherein the waveguide core comprises P2O5-SiO2.
- 22. A waveguide as claimed in any preceding claim, wherein the refractive index of the waveguide core differs from that of the lower cladding layer by at least 0.05%.
- 23. A waveguide as claimed in any preceding claim, wherein the waveguide core includes silica, and at least one Phosphorus oxide and wherein the silica to Phosphorus oxide ratio is in the range of 75 to 95 wt% silica to 5 to 25 wt% Phosphorus oxide.
- A waveguide as claimed in Claim 23, wherein the waveguide core has a silica to Phosphorus oxide ratio of 80 wt% silica to 20 wt% Phosphorus oxide.
- A waveguide as claimed in any preceding claim, wherein the thickness of the waveguide core is in the range 2 m to 60 m.
- 26. A waveguide as claimed in Claim 25, wherein the thickness of the waveguide core is 6 m.
- A waveguide as claimed in any preceding claim, wherein the lower cladding layer and the upper cladding layer refractive indices are substantially equal.

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- A waveguide as claimed in any preceding claim, wherein the lower cladding layer and the upper cladding layer comprise the same material.
- A waveguide as claimed in any preceding claim, wherein the waveguide core has a mobile ion dopant concentration higher than the mobile ion dopant concentration of the lower cladding layer or the upper cladding layer.
- 30. A method of fabricating a waveguide comprising the steps of:

providing a substrate;

forming a doped lower cladding layer by deposition; forming a doped core layer deposited on the lower cladding layer;

forming a waveguide core from the core layer; depositing a doped upper cladding layer to embed the waveguide core; and

causing mobile ion dopants included in the core layer to undergo diffusion from the waveguide core into the surrounding upper cladding layer and lower cladding layer to form an ion diffusion region around the waveguide core such that the waveguide core boundary walls are substantially smooth.

A method as claimed in Claim 30, wherein the diffusion of the said mobile dopant ions from the waveguide core is such that a waveguide core is formed which is substantially symmetric about the core axis.

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- 32. A method as claimed in either Claim 30 or 31, wherein the diffusion of the said mobile dopant ions from the waveguide core swells the boundary walls of the waveguide core.
- 33. A method as claimed in Claim 32, wherein the diffusion of the said mobile dopant ions swells the boundary walls of the waveguide core to form a substantially rounded waveguide core.
- 34. A method as claimed in Claim 33, wherein the rounded waveguide core is elliptical or circular in cross-section.
- 35. A method as claimed in any one of Claims 30 to 34, and including the step of forming a buffer layer on the substrate.
- 36. A method as claimed in Claim 35, wherein the lower cladding layer is formed on said buffer layer.
- 37. A method as claimed in any of Claims 30 to 36, wherein the steps of forming each of the lower cladding layer, the core layer and the upper cladding layer comprise the steps of:

depositing each layer; and at least partially consolidating each layer.

38. A method as claimed in Claim 37, wherein any of the lower cladding layer, the core layer and the upper cladding layer partially consolidated after deposition is fully consolidated with the full consolidation of any other of

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the lower cladding layer, the core layer or the upper cladding layer.

- A method as claimed in any of Claims 30 to 38, 39. wherein the diffusion of mobile ion dopants in the core layer occurs during the consolidation of the lower cladding layer and/or the upper cladding layer.
- A method as claimed in any of Claims 30 to 39 further comprising at least one thermal processing step after the formation of the upper cladding layer, wherein during said thermal processing of the waveguide the mobile ion dopants in the core layer undergo diffusion into the surrounding layers.
- A method as claimed in any of Claims 30 to 40, wherein the substrate comprises silicon and/or silica and/or sapphire.
- A method as claimed in any of Claims 30 to 41, wherein the buffer layer includes a thermally oxidised layer of the substrate.
- A method as claimed in any of Claims 30 to 42, wherein the buffer layer comprises doped silica.
- 44. A method as claimed in any of Claims 30 to 43, wherein the thickness of the buffer layer formed is in the range of 0.2 m to 20 m.
- A method as claimed in any one of Claims 30 to 44, wherein the lower cladding layer comprises doped silica.

- 46. A method as claimed in any one of Claims 30 to 45, wherein the lower cladding layer includes at least one Phosphorus oxide and/or Boron oxide.
- 47. A method as claimed in Claim 46, wherein the lower cladding layer includes at least one Phosphorus oxide and at least one Boron oxide and wherein the Phosphorus oxide to Boron oxide ratio is such that the lower cladding layer refractive index is substantially equal to the refractive index of the buffer layer.
- 48. A method as claimed in any of Claims 30 to 47, wherein the lower cladding layer includes silica, at least one Phosphorus oxide and at least one Boron oxide and wherein the silica; to Phosphorus oxide; to Boron oxide ratio in the range of 75 to 95 wt% silica; to 1 to 7 wt% Phosphorus oxide; to 4 to 18 wt% Boron oxide.
- 49. A method as claimed in Claim 48, wherein the lower cladding layer has a silica; to Phosphorus oxide; to Boron oxide ratio in the range of 80 to 90 wt% silica; to 2.5 to 6 wt% Phosphorus oxide; to 7.5 to 14 wt% Boron oxide.
- 50. A method as claimed in Claim 51, wherein the lower cladding layer has a silica; to Phosphorus oxide; to Boron oxide ratio of 82 wt% silica; to 5 wt% Phosphorus oxide; to 13 wt% Boron oxide.
- 51. A method as claimed in any of Claims 30 to 50, wherein the thickness of the lower cladding layer is 1 m to 20 m.

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- A method as claimed in any of Claims 30 to 51, wherein the core layer comprises doped silica.
- A method as claimed in any of Claims 30 to 51, wherein said mobile dopant ions of the waveguide core include Phosphorus and/or Fluorine and/or compounds of these elements.
- A method as claimed in any of Claims 30 to 53, wherein dopant ions of the waveguide core include Phosphorus and/or Fluorine and/or Aluminium and/or Boron and/or Germanium and/or Tin and/or Titanium and/or compounds of these elements.
- A method as claimed in any of Claims 30 to 54, wherein the core layer includes Phosphorus oxide and/or Boron oxide.
- A method as claimed in Claim 55, wherein the core layer comprises P2O5-SiO2.
- A method as claimed in any of Claims 30 to 56, wherein 57. the refractive index of the waveguide core differs from that of the lower cladding layer by at least 0.05%.
- A method as claimed in any of Claims 30 to 57, wherein the waveguide core includes silica and at least one Phosphorus oxide and wherein the silica to Phosphorus oxide ratio is in the range of 75 to 95 wt% silica to 5 to 25 wt% Phosphorus oxide.

- 59. A method as claimed in Claim 58, wherein the waveguide core has a silica to Phosphorus oxide ratio of 80 wt% silica to 20 wt% Phosphorus oxide.
- 60. A method as claimed in any of Claims 30 to 59, wherein the thickness of the waveguide core is in the range 2 m to 60 m.
- A method as claimed in Claim 60, wherein the thickness of the waveguide core is 6 m.
- 62. A method as claimed in any of claims 35 to 51, wherein said lower cladding layer and said buffer layer are formed substantially in the same step.
- A method as claimed in any of claims 37 to 62, wherein the consolidation of the lower cladding layer is at a temperature or temperatures in the range 950°C to 1400°C.
- A method as claimed in Claim 63, wherein the consolidation of the lower cladding layer is at a remperature or temperatures in the range 1100°C to 1350°C.
- A method as claimed in any of Claims 37 to 64, wherein the consolidation of the core layer is at a temperature or temperatures in the range 950°C to 1400°C.
- A method as claimed in Claim 65, wherein the consolidation of the core layer is at a temperature or temperatures in the range 1100°C to 1385°C.

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- 67. A method as claimed in any of Claims 37 to 66, wherein the consolidation of the upper cladding layer is at a temperature or temperatures in the range 950°C to 1400°C.
- A method as claimed in Claim 67, wherein the consolidation of the upper cladding layer is at a temperature or temperatures in the range 1100°C to 1350°C.
- 69. A method as claimed in any of Claims 37 to 68, wherein the temperature or temperature range at which the lower cladding layer is consolidated is greater than the temperature or temperature range at which the core is consolidated.
- A method as claimed in any of Claims 37 to 69, wherein the temperature or temperature range at which the upper cladding layer is consolidated is substantially equal to the temperature or temperature range at which the core layer is consolidated.
- A method as claimed in any of Claims 37 to 69, wherein at least one of the lower cladding layer, the core layer, and the upper cladding layer is deposited by a Flame Hydrolysis Deposition process and/or Chemical Vapour Deposition process.
- A method as claimed in Claim 71, wherein the Chemical Vapour Deposition process is a Low Pressure Chemical Vapour Deposition process or a Plasma Enhanced Chemical Vapour Deposition process.

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- 73. A method as claimed in any of Claims 37 to 72, wherein the consolidation is by fusing using a Flame Hydrolysis Deposition burner.
- 74. A method as claimed in any of Claims 37 to 72, wherein the consolidation is by fusing in a furnace.
- 75. A method as claimed in either of Claims 73 or 74, wherein the step of fusing the lower cladding layer and the step of fusing the core layer are performed simultaneously.
- 76. A method as claimed in any of Claims 30 to 75, wherein the ion diffusion region is isotropic with respect to the waveguide core.
- 77. A method as claimed in any of Claims 30 to 76, wherein the waveguide core formed from the core layer is square or rectangular in cross-section.
- 78. A waveguide as claimed in any one of Claims 1 to 29, wherein the waveguide core formed from the core layer is square or rectangular in cross-section.
- 79. A method as claimed in any of Claims 30 to 78, wherein the waveguide core is formed from the core layer using a dry etching technique and/or a photolithographic technique and/or a mechanical sawing process.
- 80. A method as claimed in Claim 79, wherein the dry etching technique comprises a reactive ion etching process and/or a plasma etching process and/or an ion milling process.

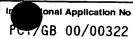


(PCT Article 18 and Rules 43 and 44)

Applicant's or agent's file reference	FOR FURTHER see Notification of	of Transmittal of International Search Report
P23051A/VSL/CLF/PPP	ACTION (Form PCT/ISA/2	220) as well as, where applicable, item 5 below.
International application No.	International filing date (day/month/year)	(Earliest) Priority Date (day/month/year)
PCT/GB 00/00322	07/02/2000	05/02/1999
Applicant		
THE UNIVERSITY COURT OF TH	HE UNIVERSITY OF et al.	
This International Search Report has been according to Article 18. A copy is being training t	prepared by this International Searching Auth nsmitted to the International Bureau.	ority and is transmitted to the applicant
This International Search Report consists o	of a total of3 sheets. a copy of each prior art document cited in this	report.
Basis of the report		
 With regard to the language, the ir language in which it was filed, unle 	nternational search was carried out on the basi less otherwise indicated under this item.	is of the international application in the
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2. Certain claims were found	d unsearchable (See Box I).	
3. Unity of Invention is lacking	ng (see Box II).	
4. With regard to the title,		
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the text has been established	ed by this Authority to read as follows:	
5. With regard to the abstract,		
the text is approved as subn the text has been establishe within one month from the d	nitted by the applicant. ed, according to Rule 38.2(b), by this Authority ate of mailing of this international search repor	as it appears in Box III. The applicant may,
6. The figure of the drawings to be publish		2e
as suggested by the applica		None of the figures.
because the applicant failed		
because this figure better ch	aracterizes the invention.	

In Jonal Application No PC-/GB 00/00322

A. CLAS	SIFICATION OF SUBJECT MATTER		
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	to International Patent Classification (IPC) or to both national	I classification and IPC	
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IPC 7	documentation searched (classification system followed by cl $602B$	lassification symbols)	
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Document	tation searched other than minimum documentation to the exte	ent that such documents are included in the fields	searched
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C. DOCUM	MENTS CONSIDERED TO BE RELEVANT		
Category °			
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X Furth	ner documents are listed in the continuation of box C.	Patent family members are listed	in anney
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		"T" later document published after the inte	mational filing date
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C.(Continua Category °	ation) DOCUMENTS CONSIDERED TO BE RELEVANT	
Category ,	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	"BURIED TI IN-DIFFUSED WAVEGUIDE ON LITHIUM NIOBATE" IBM TECHNICAL DISCLOSURE BULLETIN,US,IBM CORP. NEW YORK, vol. 33, no. 3A, 1 August 1990 (1990-08-01), page 199 XP000123902 ISSN: 0018-8689 the whole document	1-80
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